In re application of:

pplication of: Thomas A. Figura et al.

Serial No.: 09/470,650

Filed: December 22, 1999

For: USE OF A PLASMA SOURCE TO FORM A LAYER DURING THE FORMATION OF A SEMICONDUCTOR DEVICE

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H910 1-220 son Patent Harrison

Group Art Unit: 2813

Examiner: Lisa Kilday

Atty. Docket: 94-0280.04

Certificate of Mailing (37 C.F.R.§ 1.8)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on the date below:

11/8/01

Signature florme

PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136(a)

RECEIVED

Commissioner for Patents Washington, D.C. 20231

BEST AVAILABLE COPY

Dear Sir:

Applicants mereby retition to extend the period for response to the Office Action mailed August 6, 2001 for one (1) month, from November 5, 2001 to December 6, 2001.

Accordingly, the requisite fee is \$ 110. The Commissioner is requested to charge this fee, and any additional fee which may be required to Micron Technology, Inc. Deposit Account 13-3092, Order No. 94-0280.04. A duplicate copy of this petition is enclosed.

Respectfully submitted,

Date: 11 7/1

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